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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:
Gaillard, et al.

Serial No.: 09/706,298

Confirmation No.: 6722

Filed: November 3, 2000

For: Novel Integration Scheme for Dual
Damascene StructureCommissioner for Patents
Washington, D.C. 20231§
§ Group Art Unit: 1765

§ Examiner: V. Perez Ramos

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CERTIFICATE OF MAILING 37 CFR 1.8	
I hereby certify that this correspondence is being deposited on <u>February 20, 2003</u> with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231	
<u>2/20/03</u>	<u>Kurt R. Zehn</u>
Date	Signature

Dear Sir:

RESPONSE TO OFFICE ACTION DATED NOVEMBER 21, 2002

In response to the Office Action dated November 21, 2002, having a shortened statutory period for response set to expire on February 21, 2003, Applicant requests entry and consideration of the following amendments and remarks. Although Applicant believes that no fee is due in conjunction with this response, the Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/AMAT/4564/DSM/LOW K/JW, for any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.

IN THE CLAIMS:

Please amend the claims as follows:

1. (Amended) A method for processing a substrate, comprising:
 - (a) forming a feature definition in a dielectric material deposited on a surface **A** of a substrate;

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TO 1765
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